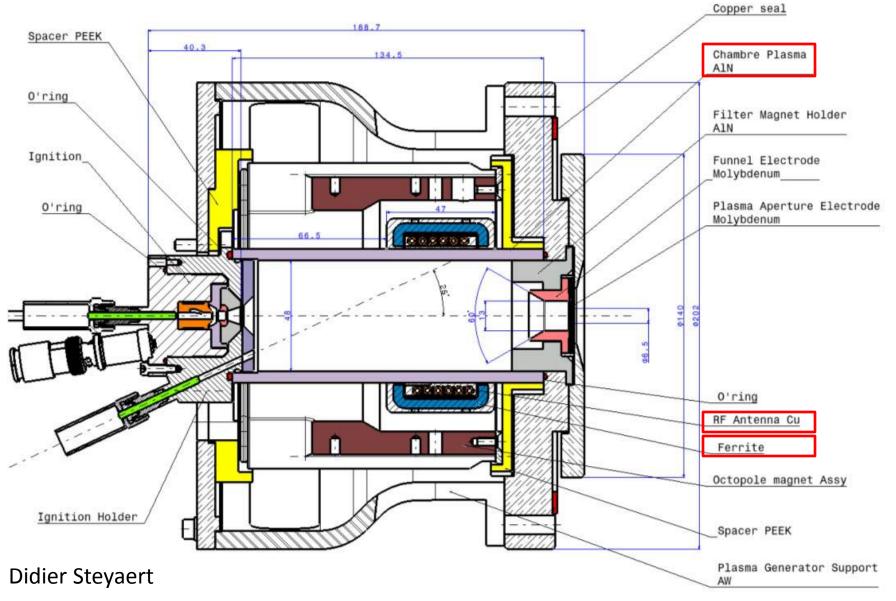
RF fields simulations

Alexej Grudiev, BE-RF 14/11/2013 Linac4 Ion Source Review, CERN

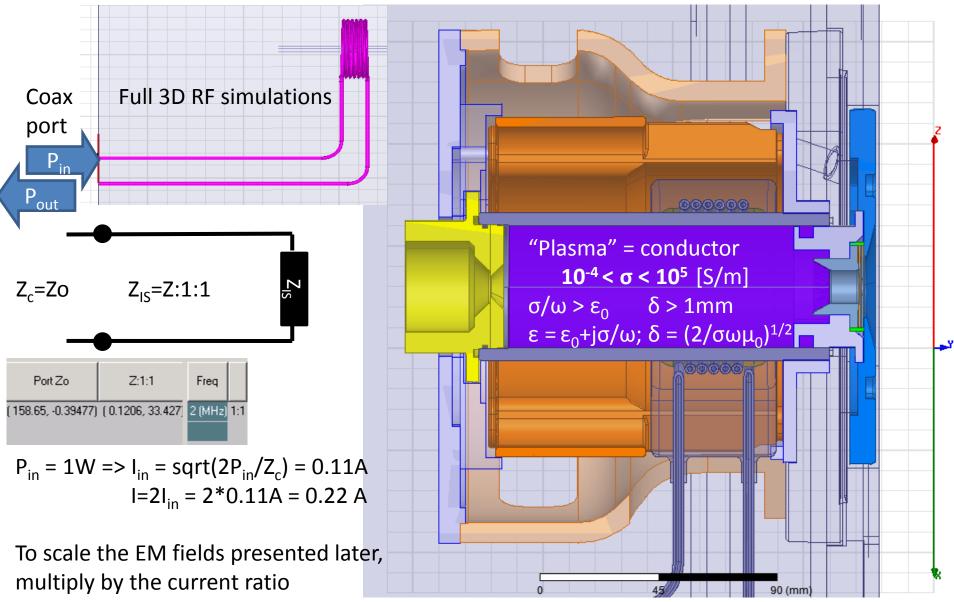
Outline

- RF field simulations setup
- Plasma model as a conductor
- Surface electric field enhancement
- EM field distribution in plasma chamber
- Ion source Impedance
- Comparison with measurements
- Variation of the ion source geometry
- Conclusions

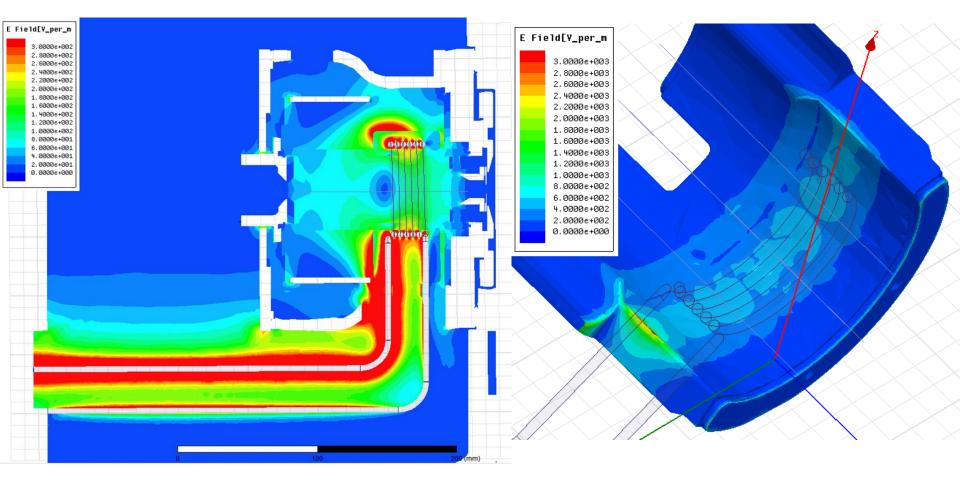
CAD 3D model of IS-01



RF simulation setup (HFSS)

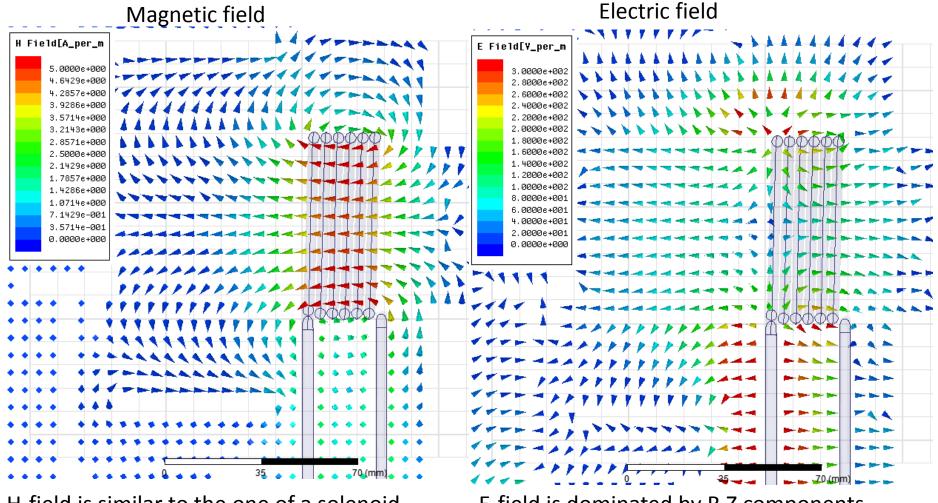


Surface electric field enhancement



Max E-field on the surface of the Cu octupole envelop for 220 A coil current is about 3 MV/m, same as air discharge threshold. This due to sharp edge close to the coil.

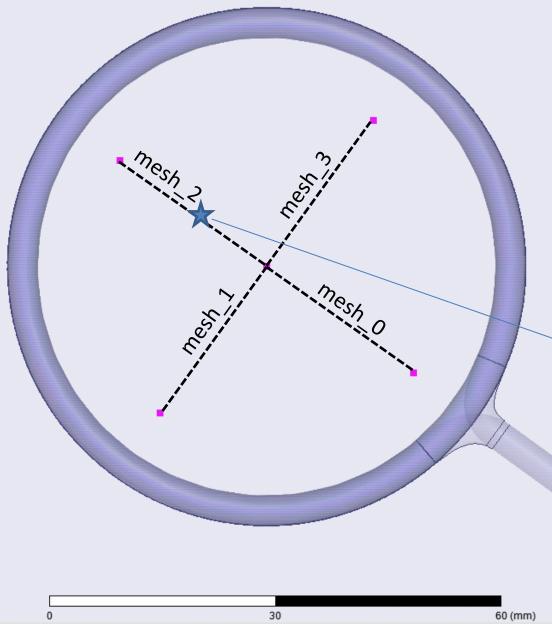
EM field distribution in plasma chamber region, $\sigma=0$



H-field is similar to the one of a solenoid

E-field is dominated by R,Z components. It is mainly capacitive

Field map for plasma simulations

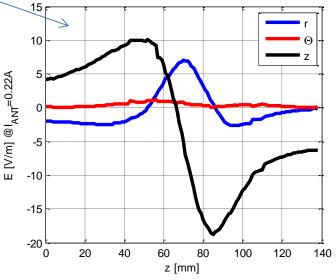


Averaging the field over 4 meshes remove radial and azimuthal components on axis r=0 and make the distribution quasi 2D.

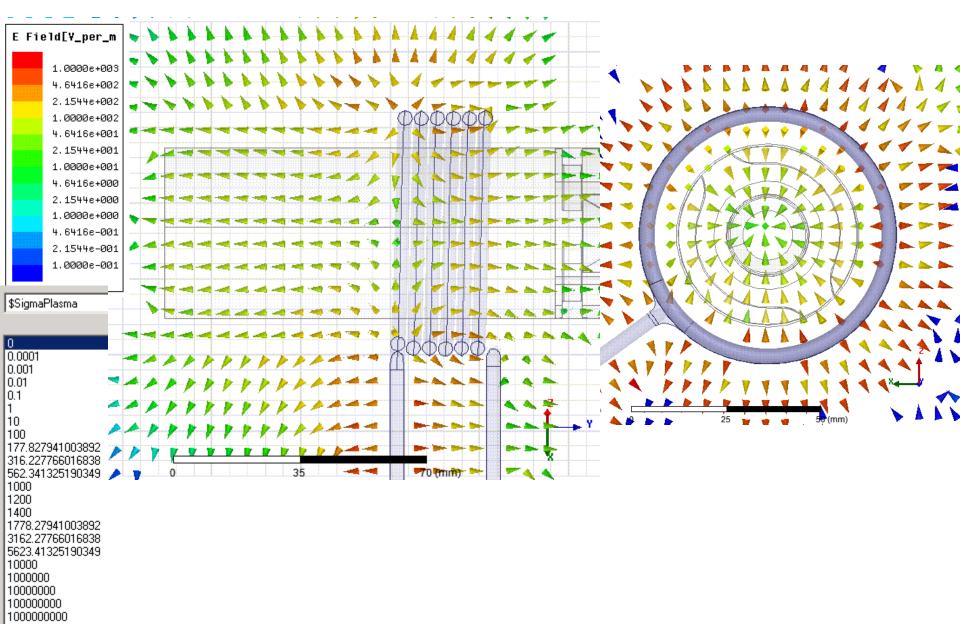
To be used in the plasma simulation code with 2D field representation.

Field = 1/4*[

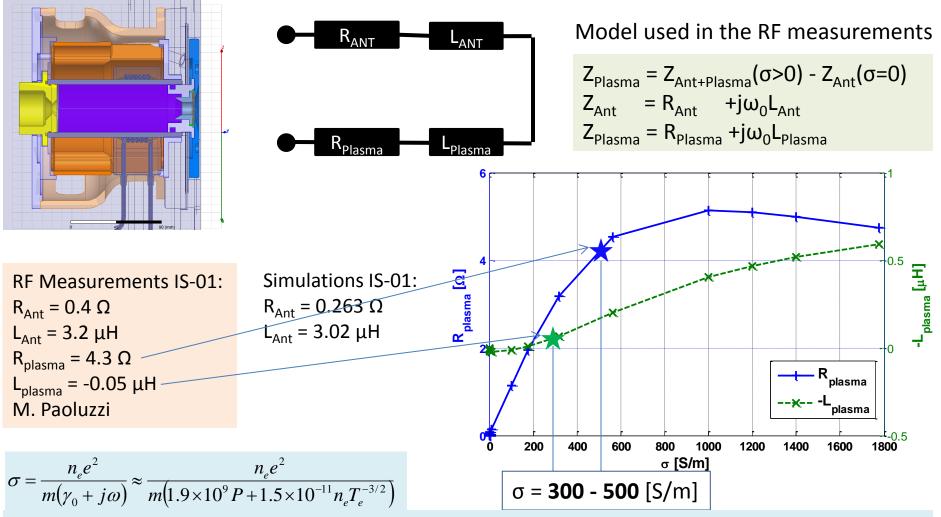
field(mesh_0)+field(mesh_1)+
field(mesh_2)+field(mesh_3)]



E-field distribution in plasma chamber. $\sigma > 0$

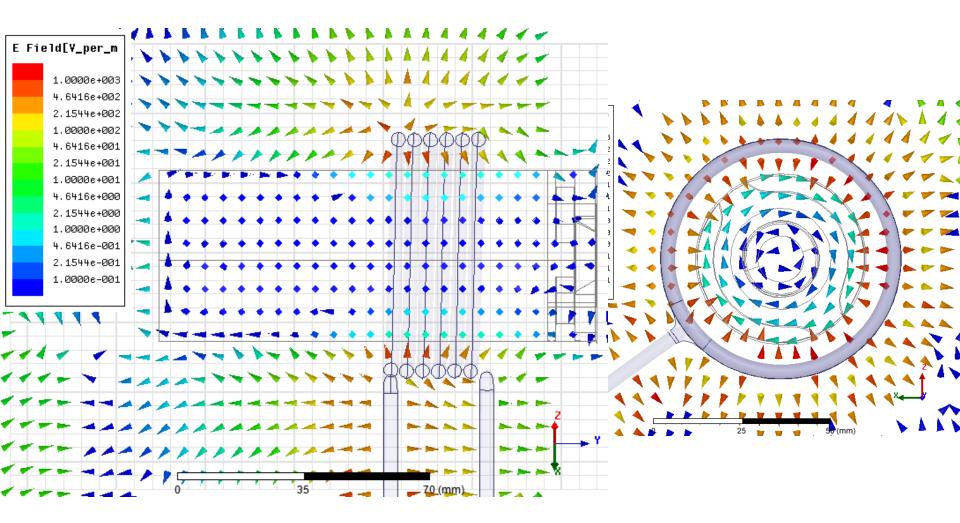


Ion source impedance



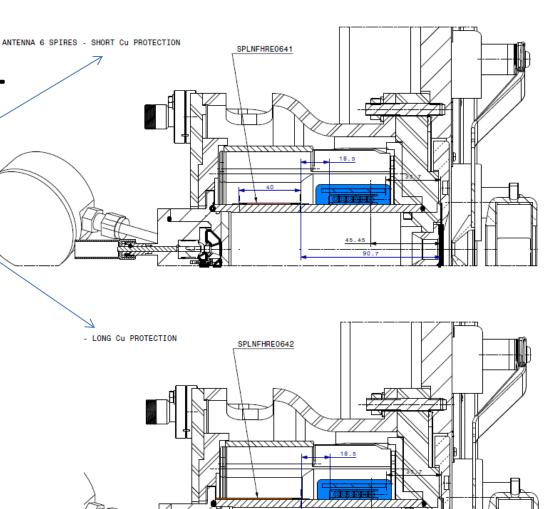
Plasma measurements (**SPL-IS**): H₂ pressure ~ 20 mTorr, n_e ~ $10^{18} - 10^{19}$ m⁻³ and T_e ~ 10 eV. => It gives an estimate of the conductivity of **730** - **6600** S/m for the above given density range R. Scrivens

E-field distribution in plasma chamber, $\sigma = 1000$ S/m

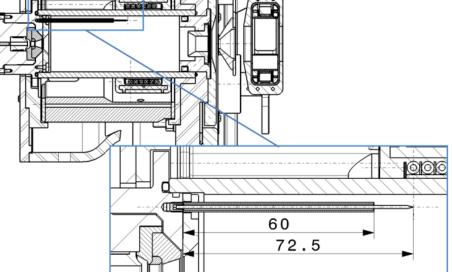


Variations: SET 1

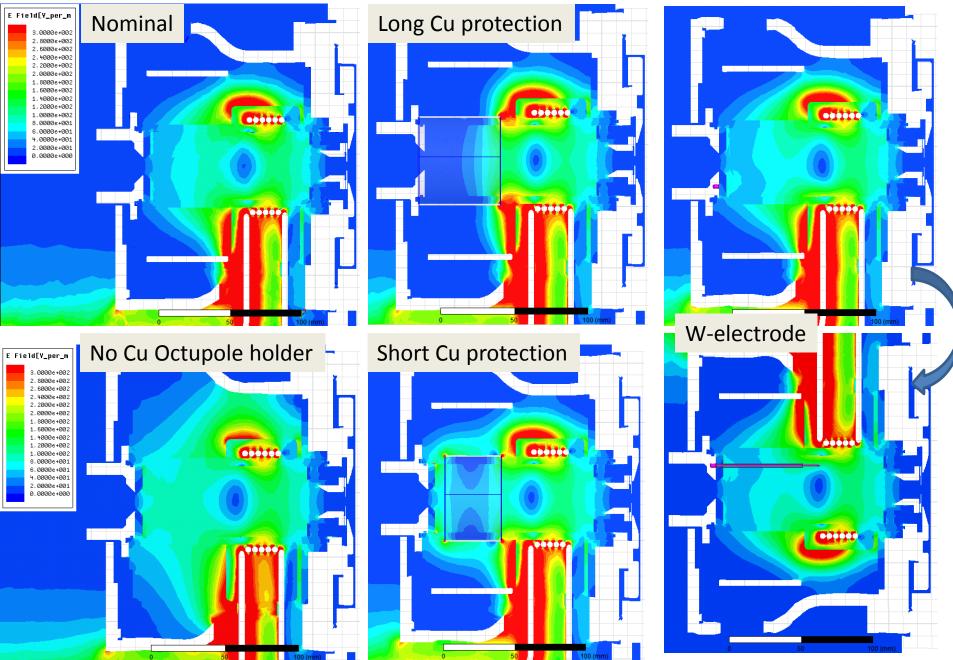
- 1. No Cu octupole holder
- 2. Long Cu protection
- 3. Short Cu protection -
- 4. W-electrode



90



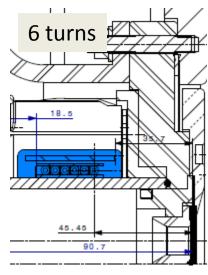
Variations SET 1: E-field distribution

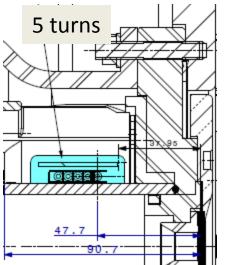


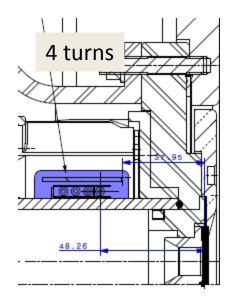
Variation of number of antenna turns

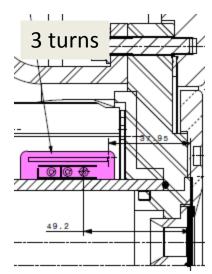
- 1. Nominal, 6 turns
- 2. 5 turns
- 3. 4 turns
- 4. 3 turns

N.B. for 5,4,3 turns the size of epoxy and ferrites are a bit smaller. The same materials are used

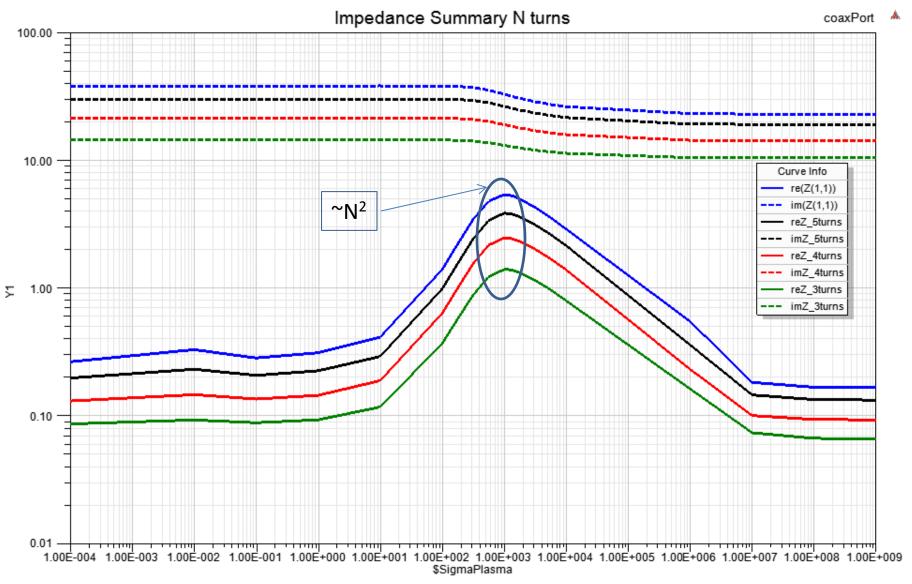




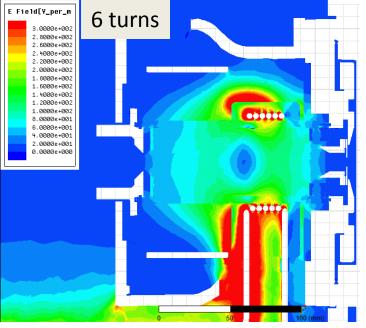


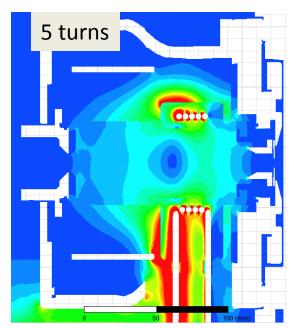


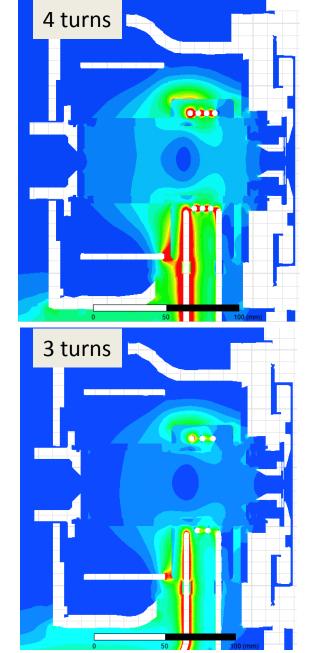
Variation of number of turns: impedance



Variation of N turns: E-field distribution







Plasma

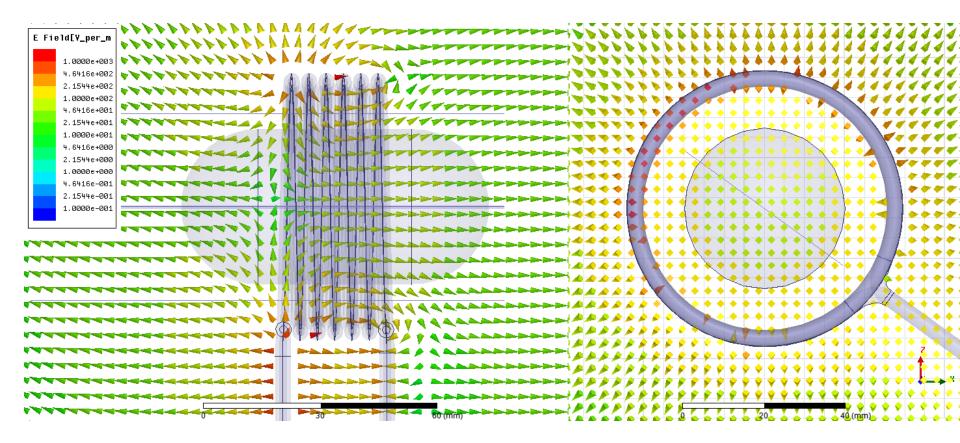
code

Conclusions

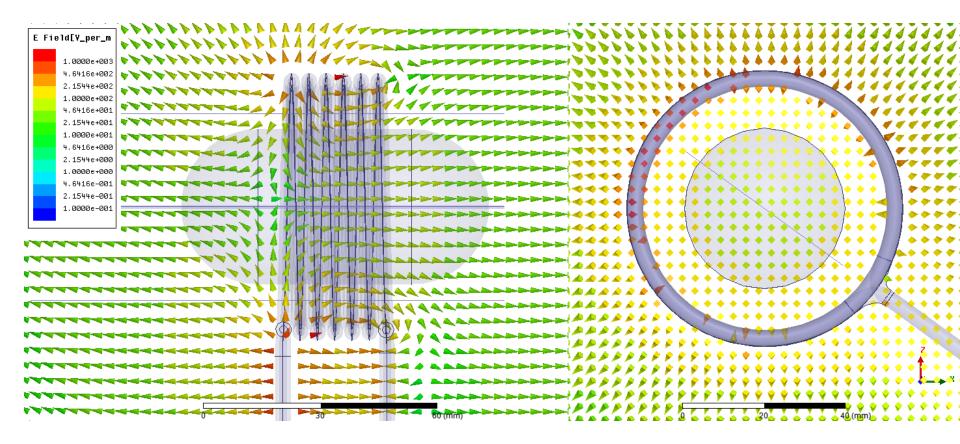
- Full 3D model with realistic material parameters is implemented and simulated using RF code HFSS
- Plasma is modelled as a conductor
- Surface electric field is calculated and compared to discharge limited values
- Without plasma electric field distribution in the plasma chamber is dominated by R,Z components, capacitive electric field
- EM field maps has been calculated for the plasma simulation code
- Impedance of the ion source as a function of "plasma" conductivity is calculated and compared to the RF measurements results
- Matching simulated and measured impedance values gives plasma conductivity which agrees with the one calculated from measured plasma parameters
- Several variations of the IS-01 has been simulated

Spare slides

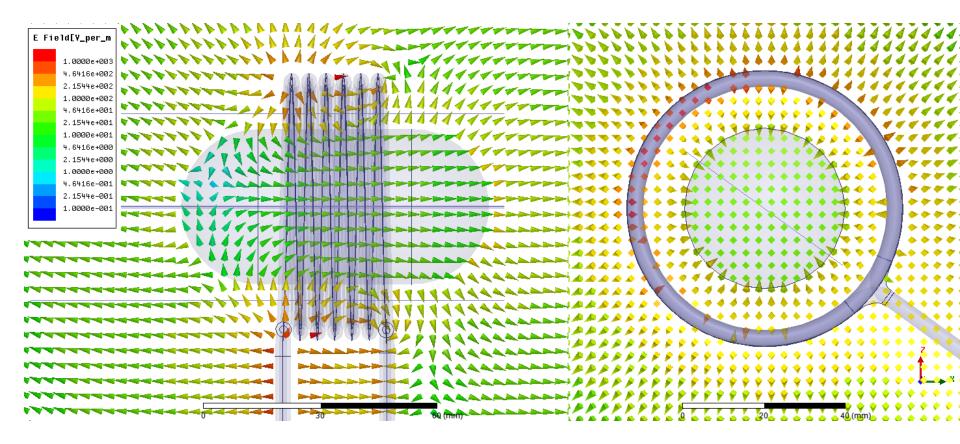
E-field: antenna + "plasma" ($\sigma = 0$ S/m)



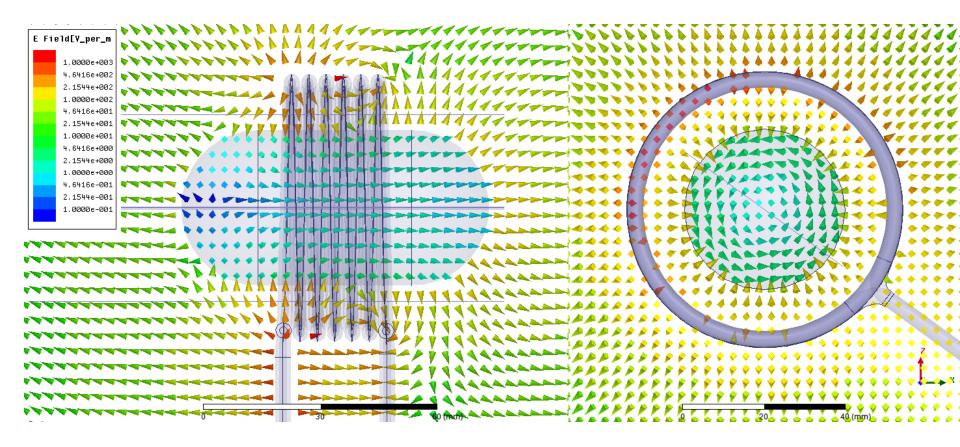
E-field: antenna + "plasma" (σ = 1e-4 S/m)



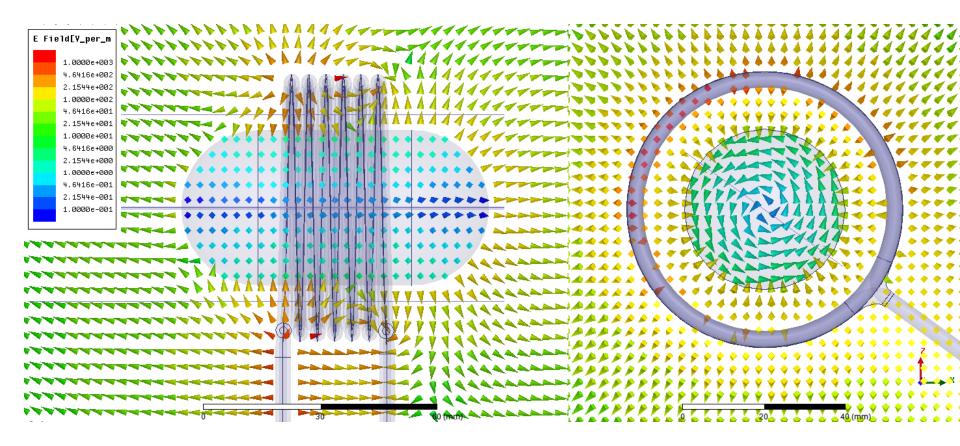
E-field: antenna + "plasma" (σ = 1e-3 S/m)



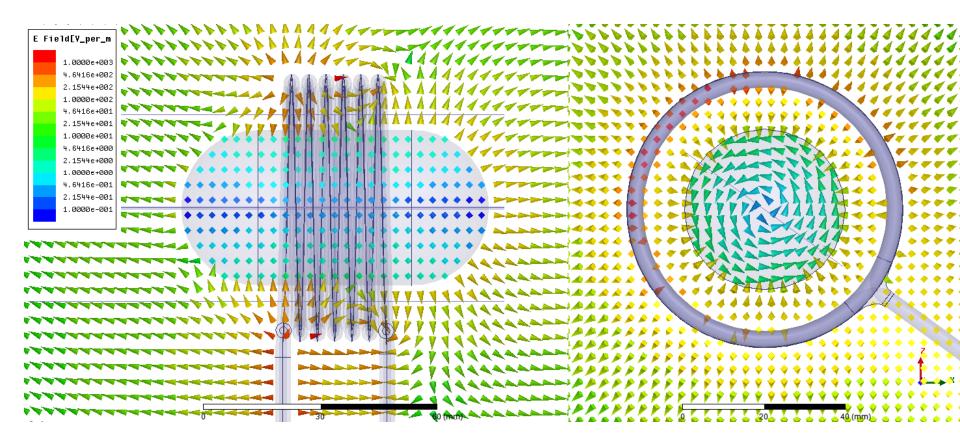
E-field: antenna + "plasma" (σ = 1e-2 S/m)



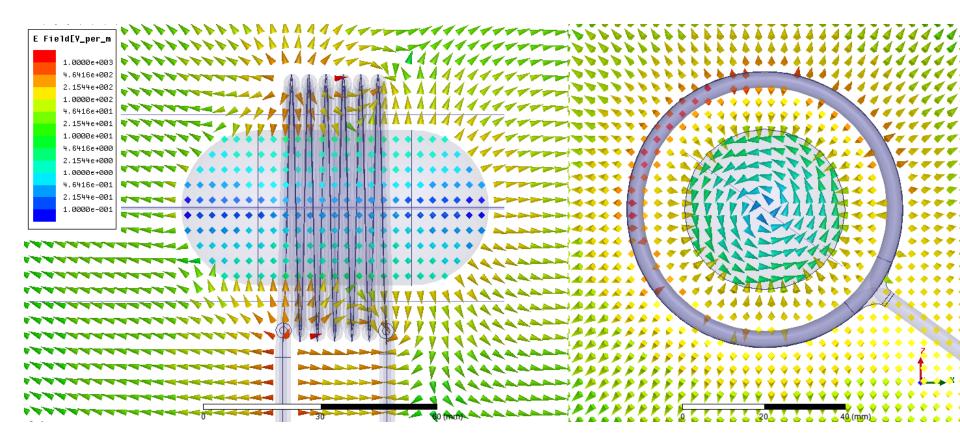
E-field: antenna + "plasma" (σ = 1e-1 S/m)



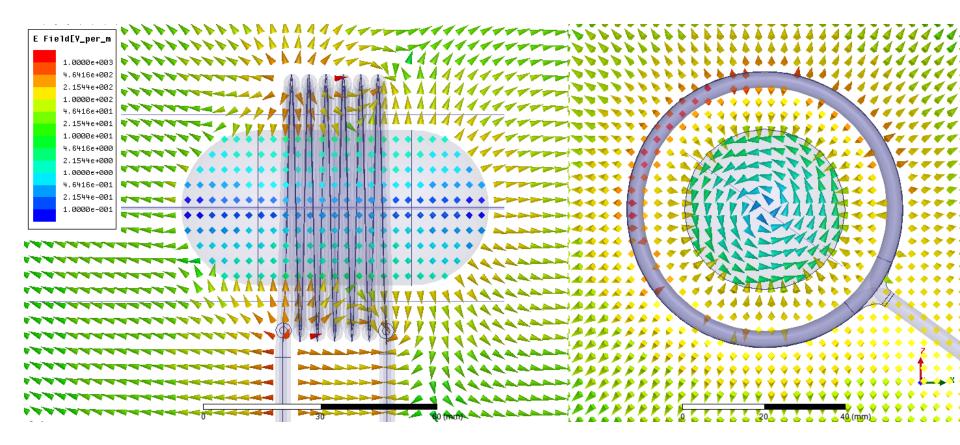
E-field: antenna + "plasma" (σ = 1e-0 S/m)



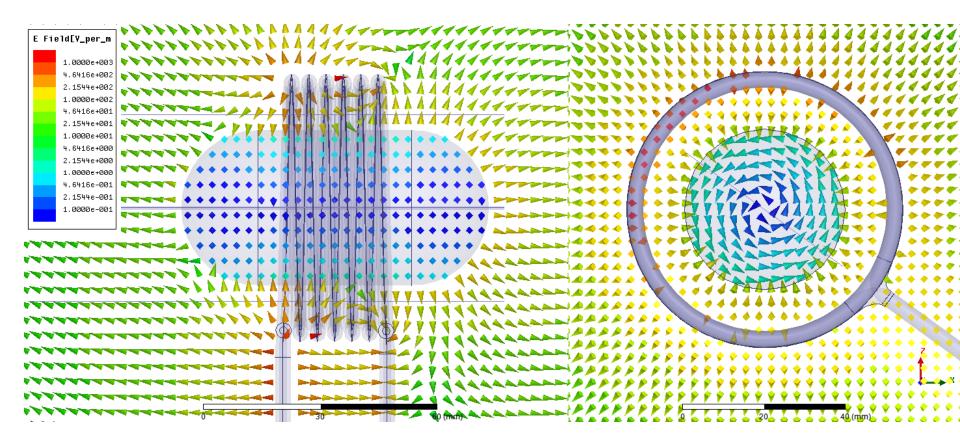
E-field: antenna + "plasma" (σ = 1e+1 S/m)



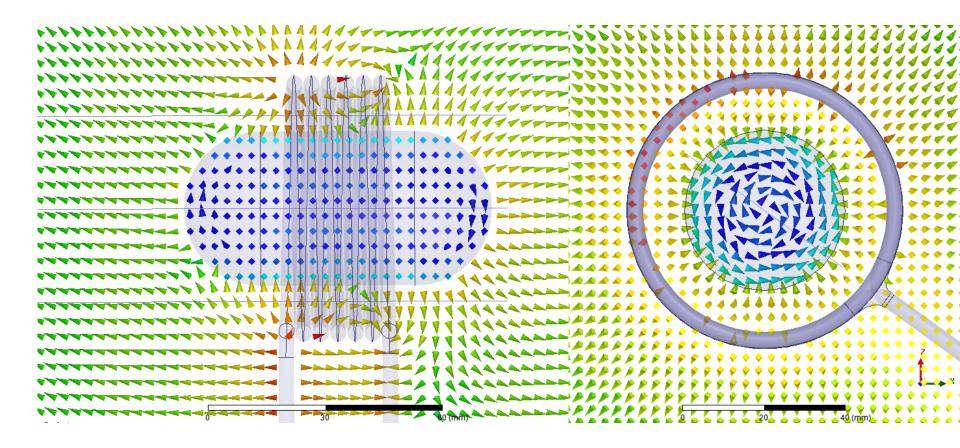
E-field: antenna + "plasma" (σ = 1e+2 S/m)



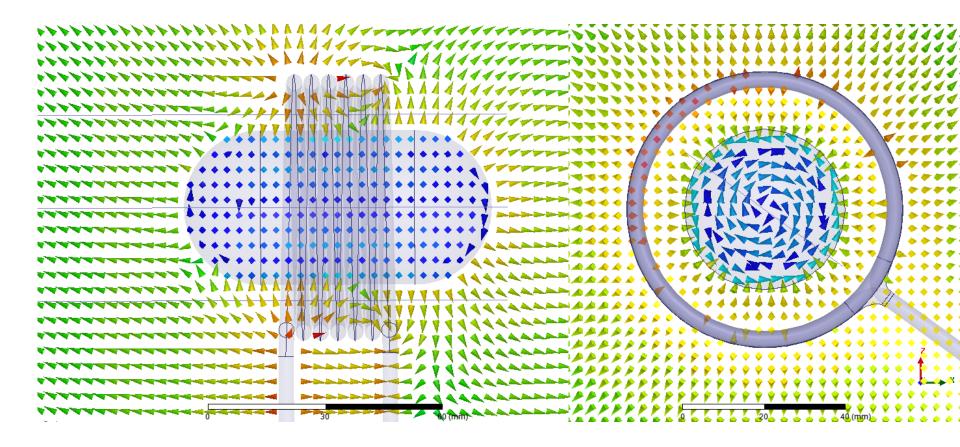
E-field: antenna + "plasma" (σ = 1e+3 S/m)



E-field: antenna + "plasma" (σ = 2e+3 S/m)



E-field: antenna + "plasma" (σ = 3e+3 S/m)



E-field: antenna + "plasma" (σ = 1e+4 S/m)

